

FIG. 1

Figure 2. Thickness: PDC results for the medium deposition process.

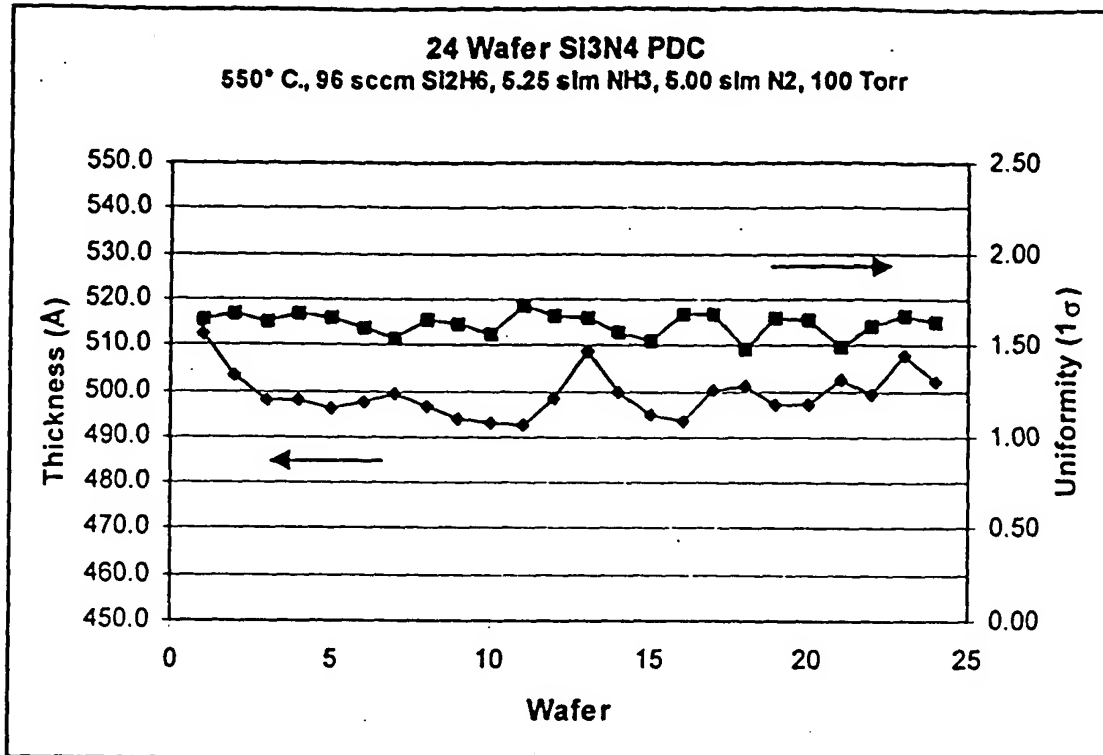
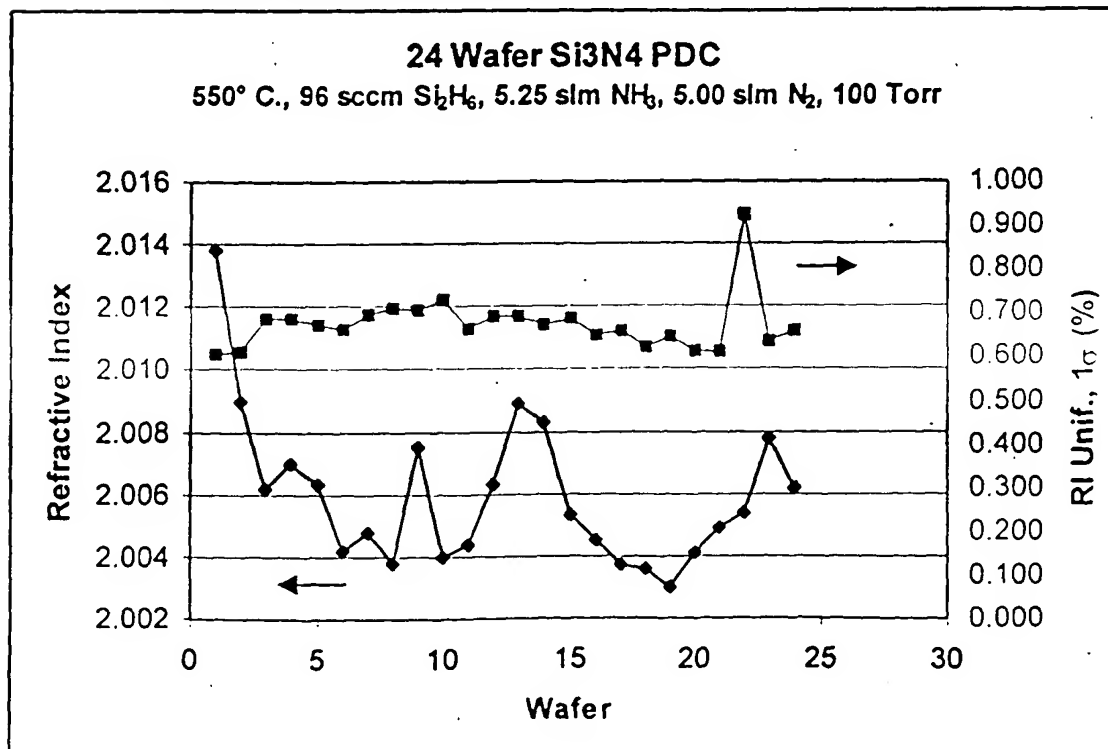
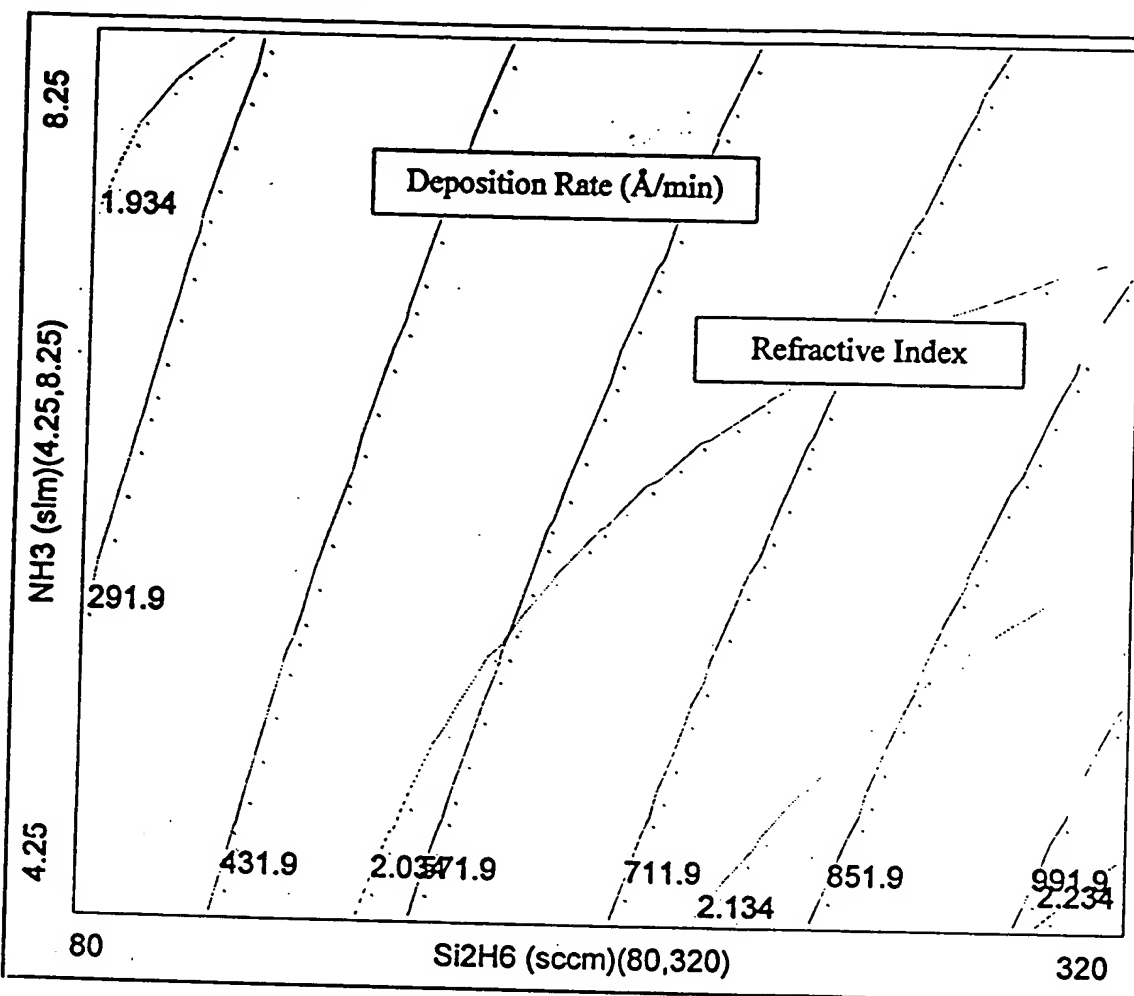
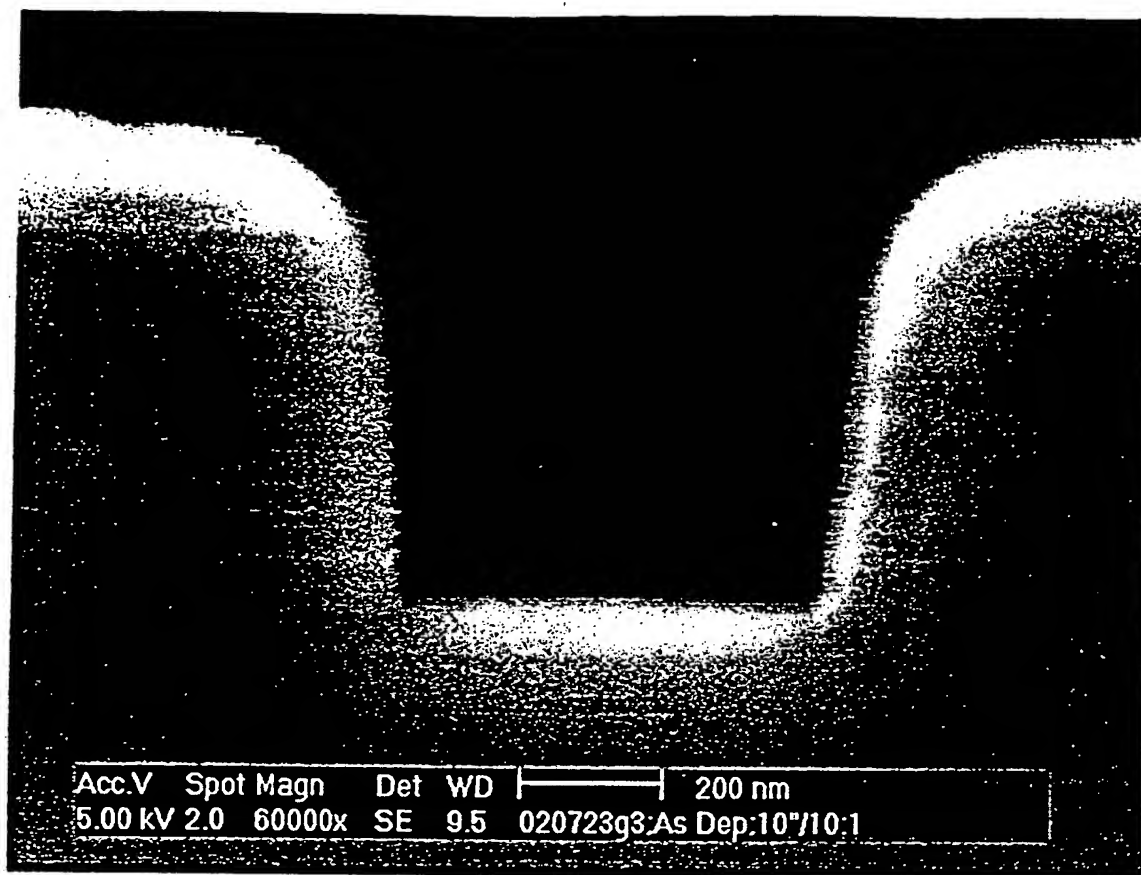


Figure 3. RI PDC results for the medium deposition rate process.







550°C Si₂H₆-based silicon nitride (deposition rate: 500 Å/min)

FIGURE 5